

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 03-094070

(43)Date of publication of application : 18.04.1991

(51)Int.Cl.

C23C 16/54

C23C 16/44

H01L 21/205

H01L 21/285

H01L 21/31

(21)Application number : 01-229844

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(22)Date of filing : 05.09.1989

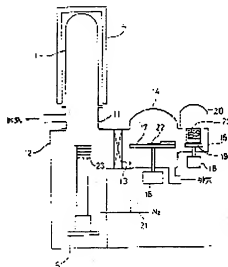
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## (54) CVD DEVICE

## (57)Abstract:

PURPOSE: To prevent the oxidation after CVD and contamination with dust by providing a gate valve between a load-locking chamber and a load-locking spare chamber and conveying a wafer from a cassette into a reaction chamber in an airtight vessel.

CONSTITUTION: A gate valve 13 provided between the load-locking chamber 12 and the load-locking spare chamber 14 is closed, and the vertical reaction chamber 1 and the load-locking chamber 12 connected to the lower part of the chamber 1 are airtightly closed. A cassette changed with a wafer 23 is placed on the cassette receiver 19 of a cassette elevator 18. The spare chamber 14 and a cassette chamber 15 are then evacuated. The valve 13 is opened, and the wafer 23 is transferred to an elevator mechanism 5 by a wafer transfer machine 16. The valve 13 is then closed, the reaction chamber 1 and the load-locking chamber 12 are supplied with a gaseous reactant, and CVD is applied.



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the  
examiner's decision of rejection or application  
converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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